### **Stress-induced anisotropic diffusion in alloys: Complex Si solute flow near a dislocation core in Ni**

Venkat Manga, Zebo Li, Thomas Garnier, Maylise Nastar, Pascal Bellon, Robert Averback, Dallas R. Trinkle

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Goal: Predict solute and defect evolution near a dislocation

Transport of point defects near dislocations (sinks)

# Under irradiation: continuous transport of defect fluxes to sinks

- Coupling of defects and solutes fluxes?
- Segregation, precipitation, creep?

#### Stresses of dislocation and applied

- Inhomogeneous driving forces
- Inhomogeneous anisotropic mobilities

System: substitutional Si in Ni

#### Approach:

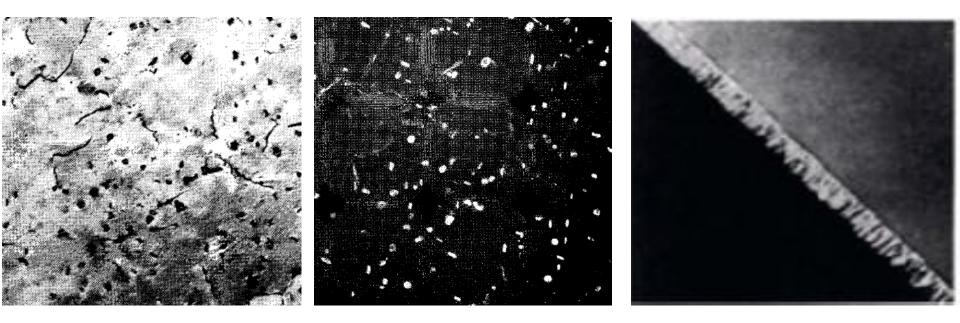
- Ab initio calculation of migration barriers
- Self-consistent mean-field method



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# Irradiation-induced precipitation

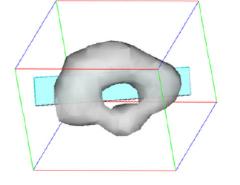
- Undersaturated Ni-Si alloys
  - Precipitation of  $Ni_3Si$  precipitates induced by vacancy flux to sinks



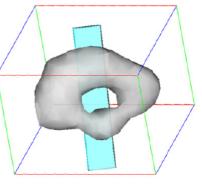
#### Dislocations

#### Grain boundaries

Barbu and Ardell, *Scripta metal.*,**9**,(1975) Rehn *et al., Phys. Rev. B*, **30** (1984) Composition profiles at dislocation loop in CP304 post-irradiation



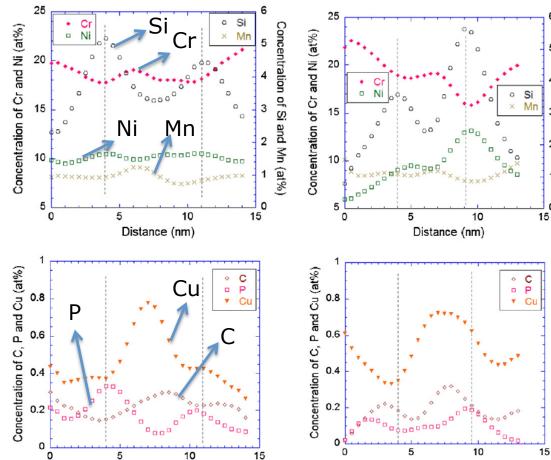
Distance (nm)



Distance (nm)

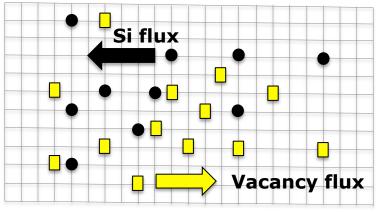
Was *et al.* Acta Mater. **59**, 1220 (2011)

Enrichment of Si, Ni and P at the dislocation
 Cr and Mn are depleted
 Similar segregation behavior to grain boundaries



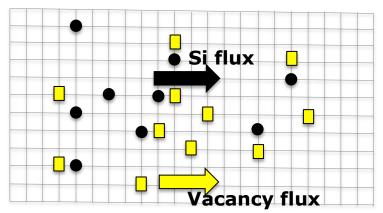
# Solute drag: vacancy and solute flux coupling

vacancy-solute exchange dominant

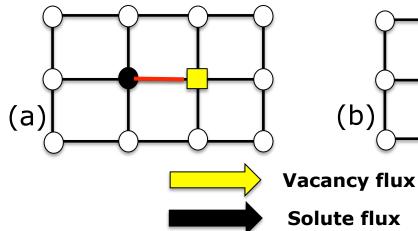


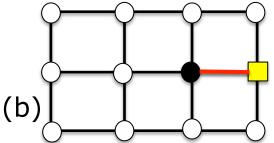
 $J_V / J_{Si}$  **negative** if solutes and vacancies move in opposite directions

# solute drag by vacancy complex



 $J_{\rm V}$  /  $J_{\rm Si}$  **positive** if solutes and vacancies move in same direction





#### The Onsager flux equations

Linear relation between fluxes and the driving forces (Allnatt1993)

 $J_i = \sum_j L_{ij} X_j$  (i,j=1,2,...)  $L_{ij}$ : The phenomenological coefficients; X : the driving force (for e.g. gradient of chemical potential)

In a binary system Ni-Si

$$\begin{split} J_{\mathrm{Ni}} &= L_{\mathrm{NiNi}} \nabla \mu_{\mathrm{Ni}} + L_{\mathrm{NiSi}} \nabla \mu_{\mathrm{Si}} + L_{\mathrm{NiV}} \nabla \mu_{\mathrm{V}} & \sum_{i} J_{i} = 0 \\ J_{\mathrm{Si}} &= L_{\mathrm{SiSi}} \nabla \mu_{\mathrm{Si}} + L_{\mathrm{SiNi}} \nabla \mu_{\mathrm{Ni}} + L_{\mathrm{SiV}} \nabla \mu_{\mathrm{V}} \\ J_{\mathrm{V}} &= L_{\mathrm{VSi}} \nabla \mu_{\mathrm{Si}} + L_{\mathrm{VNi}} \nabla \mu_{\mathrm{Ni}} + L_{\mathrm{VV}} \nabla \mu_{\mathrm{V}} \end{split}$$
 vacancy-mediated diffusion

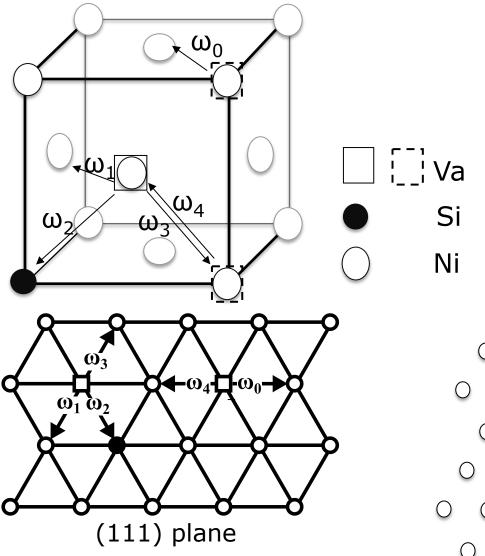
Quantities of interest from phenomenological coefficients

**Diffusion coefficients**  $D_{\text{Si}} = \frac{kT}{n} (\frac{L_{\text{SiSi}}}{c_{\text{Si}}} - \frac{L_{\text{NiSi}}}{c_{\text{Ni}}})(1 + \frac{\partial \ln \gamma_{\text{Si}}}{\partial \ln c_{\text{Si}}}) \longrightarrow \text{In the dilute} \quad D_{\text{Si}} = \frac{kT}{n_{\text{Si}}} L_{\text{SiSi}}$   $\gamma_{\text{si}} - \text{activity coefficient}$   $c_{\text{si}} - \text{concentration of Si}$  **Solute drag**  $L_{\text{SiV}} = -L_{\text{SiSi}} - L_{\text{NiSi}}$   $G = \frac{L_{NiSi}}{L_{SiSi}}$  $L_{\text{SiV}} - \text{negative if solutes and vacancies move in opposite directions}$ 

- positive if **solute-drag** is predominant

Allnatt: Atomic transport in solids (1993)

# Vacancy mediated diffusion in FCC Ni

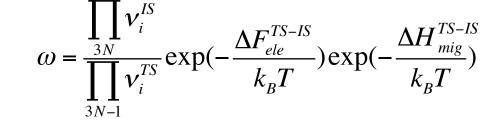


	Jump type
ω	self-diffusion jump
ω <sub>1</sub>	vacancy-exchange
ω2	impurity jump
ω <sub>3</sub>	dissociation jump
ω <sub>4</sub>	association jump

 $\omega_3 << \omega_1$ : Si-Va tightly bound = Si in the same direction as vacancies  $\omega_3 \approx \omega_1$ : Si-Va no strong interaction = Si flows opposite to vacancies

Jump frequencies: harmonic transition state theory

atomic jump freq.

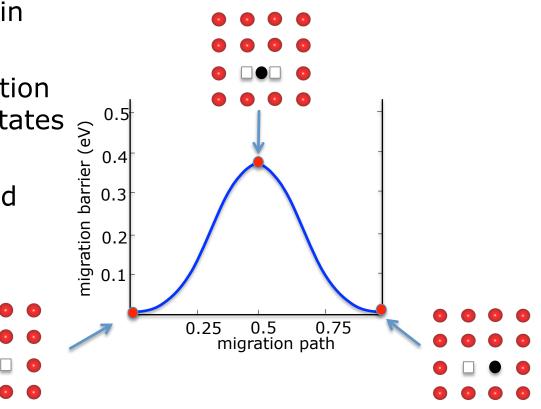


phonon frequency

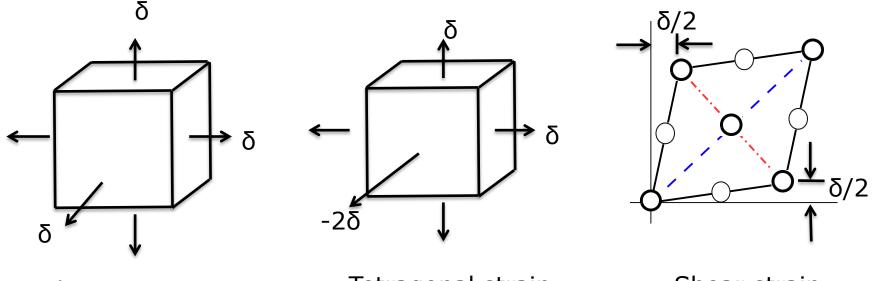
enthalpy of migration

First-Principles calculation of

- Phonon frequencies `v' within harmonic approximation
- Thermal electronic contribution from electronic density of states s
- Enthalpy of migration from nudged-elastic band method



## Phenomenological coefficients modified by strains



Volumetric strain

Tetragonal strain

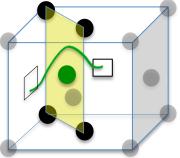
Shear strain

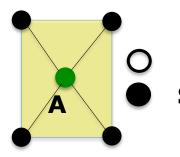
$$\begin{split} L_{ij}(\delta) &: \text{phenomenological coefficients as a function of strain} \\ \omega_j(\delta) &= v^*(\delta) \cdot \exp\left(\frac{-\Delta E_j(\delta)}{kT}\right) \longrightarrow \text{From ab initio calculations} \\ L_{\text{SiV}}(\omega_0, \omega_1, \omega_2 ...) \longrightarrow \text{From self-consistent mean-field}^{(1,2)} \\ L_{\text{SiV}}(\delta) &= L_{\text{SiV}}(0) + \frac{dL_{\text{SiV}}}{d\delta} \Big|_{\delta=0} \cdot \delta \end{split}$$

1. Nastar et al. Phil. Mag. (2005), 2. Nastar et al. Phil. Mag. A (2000)

# Vacancy-mediated diffusion with hydrostatic strain

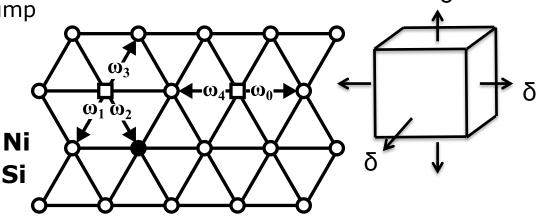
- The planar cage for any <110> jump
- Strain on the cage area and its relation to the barriers





<110> jumps cage at the transition state

Strain on the cage diagonal :  $\boldsymbol{\delta}$ 



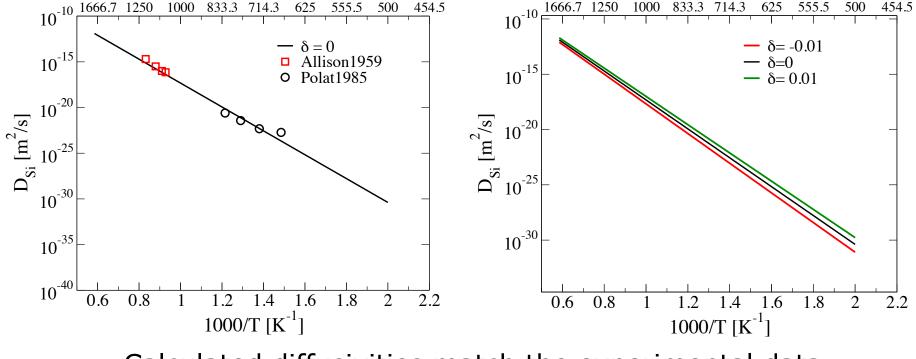
- 5-frequency model for FCC
- No change in the symmetry under volumetric strain

	Jump type		Tension $(\delta=0.01)$	δ=0	Compression $(\delta = -0.01)$
ω <sub>0</sub>	self-diffusion jump	[/	1.04 ≈ 1.10-0.07	1.10	1.17 = 1.10 + 0.07
$\omega_1$	vacancy-exchange	[eV]	0.99 ≈ 1.05-0.07	1.05	1.12 = 1.05 + 0.07
ω <sub>2</sub>	impurity jump	iers	0.87 = 0.94-0.07	0.94	1.01 = 0.94 + 0.07
ω <sub>3</sub>	dissociation jump	arr	1.20 = 1.27 - 0.07	1.27	1.34 = 1.27 + 0.07
ω <sub>4</sub>	association jump	B	1.10 ≈ 1.16-0.07	1.16	1.23 = 1.16 + 0.07

All barriers change by the same quantity with strain:  $\Delta E_i(\delta) \approx \Delta E_i(0) - (7 \text{eV})\delta$ 

# Diffusion coefficient of Si in Ni: hydrostatic strain

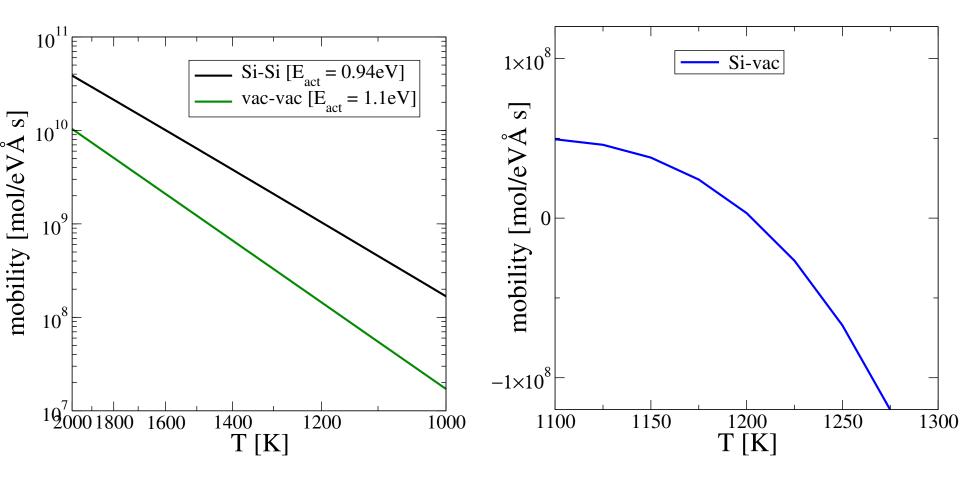
- Calculations similar to the 5-frequency model
  - 14 frequencies when including 3<sup>rd</sup> neighbor interaction<sup>4</sup>
  - 1<sup>st</sup> neigh. 0.1eV attraction, 3<sup>rd</sup> neigh. 0.05eV repulsion
  - Most hop barriers follow kinetically-resolved activation barrier approx.: forward-reverse average ≈ constant
- Same change in activation energies with stress for all jumps



Calculated diffusivities match the experimental data

# Mobility coefficients of Si in Ni: solute drag

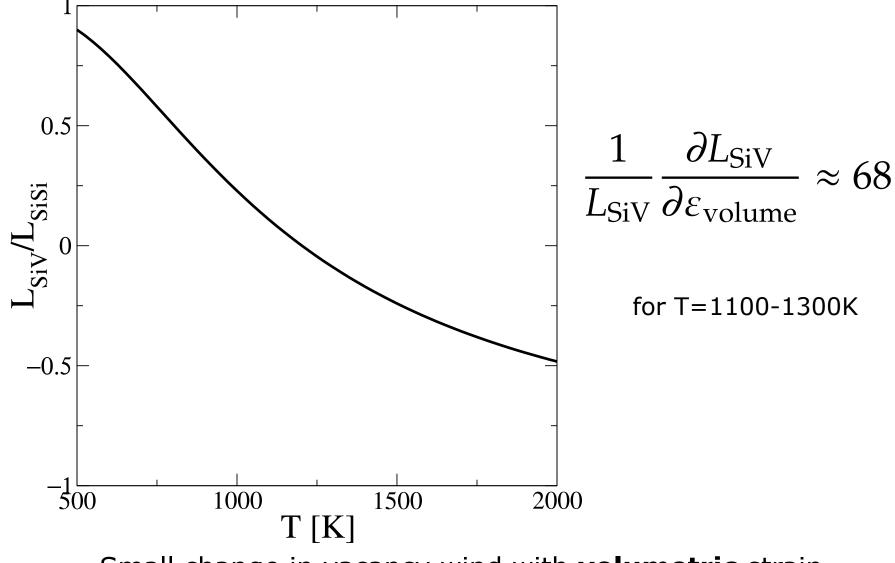
• From the 14 frequency model



Small change in vacancy wind with **volumetric** strain

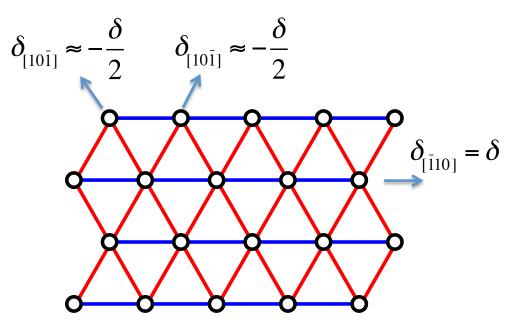
# Mobility coefficients of Si in Ni: vacancy wind

• From the 5 frequency model: crossover temperature of 1200K



Small change in vacancy wind with **volumetric** strain

## Migration barriers and jump frequencies: tetragonal strain



(111) Plane : Tetragonal strain

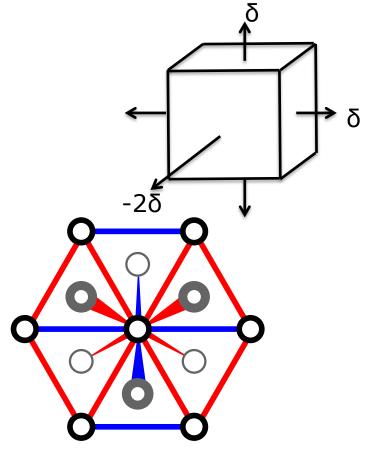
12 first nearest neighbor(NN) bonds break symmetry <110>: Red (8) and Blue (4)

 $\delta{>}0$  – Blue bonds are longer than Red

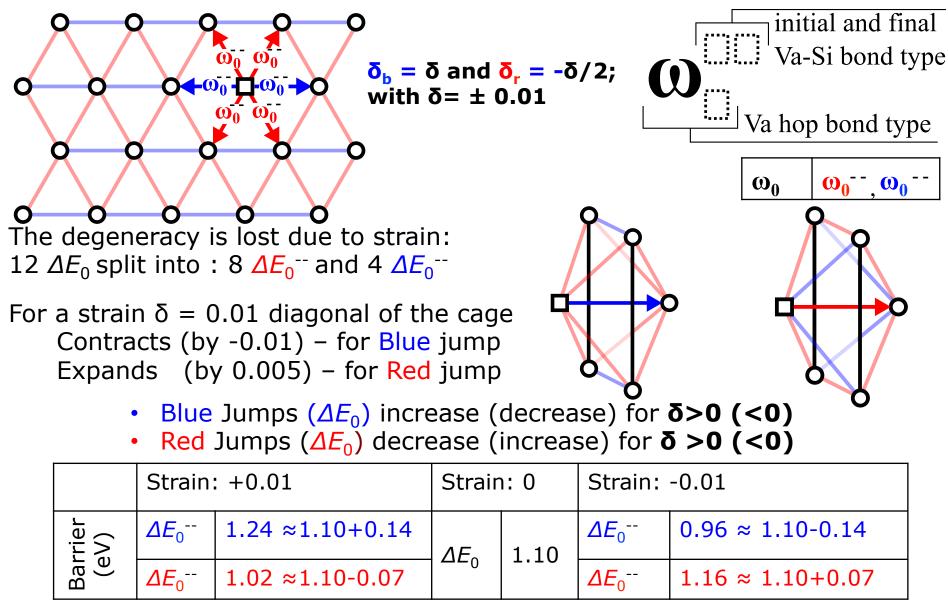
 $\delta < 0$  – Blue bonds are shorter than Red

 $\frac{\mathbf{\delta}_{b}}{\mathbf{\delta}_{r}} = \mathbf{\delta}$ 

Needs 15 (44) frequencies to calculate  $L_{ij}$  matrix

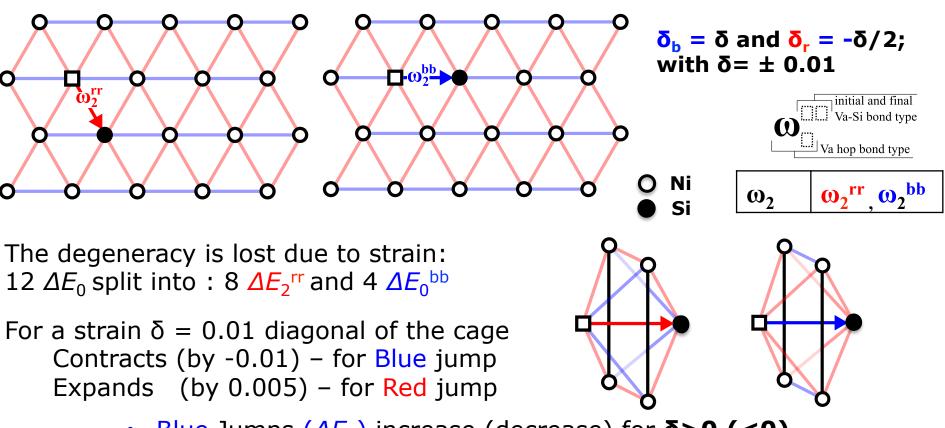


Ni self-diffusion jumps ( $\omega_0$  –type) under tetragonal strain



 $\Delta E_0(\delta) \approx \Delta E_0(0) - (14 \text{eV}) \delta_{\text{diagonal}}$ 

# Si-vacancy exchange ( $\omega_2$ –type) under tetragonal strain

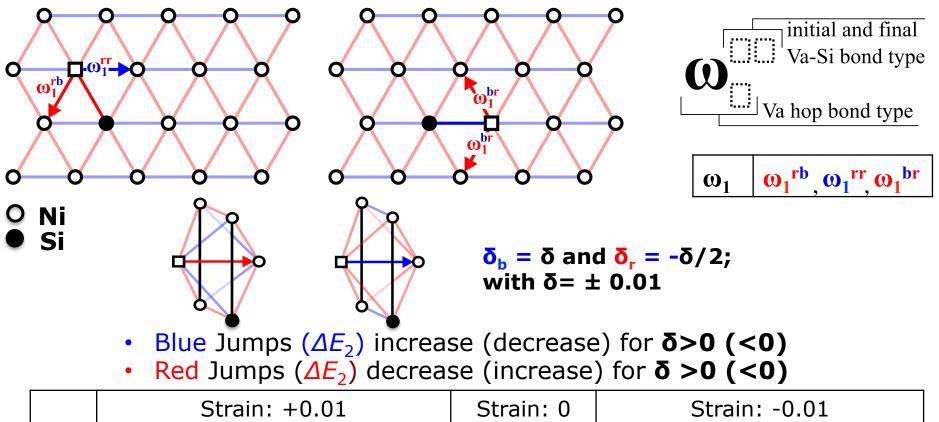


- Blue Jumps ( $\Delta E_2$ ) increase (decrease) for  $\delta > 0$  (<0)
- Red Jumps ( $\Delta E_2$ ) decrease (increase) for  $\delta > 0$  (<0)

	Strain: +0.01		Strain: 0		Strain: -0.01	
'ier /)	$\Delta E_2^{bb}$	1.07 ≈ 0.94+0.14			$\Delta E_2^{bb}$	0.80 ≈ 0.94-0.14
Barr (e\	$\Delta E_2^{\rm rr}$	0.86 ≈ 0.94-0.07	$\Delta E_2$	0.94	$\Delta E_2^{\rm rr}$	1.00 ≈ 0.94+0.07

$$\Delta E_2(\delta) \approx \Delta E_2(0) - (14 \text{eV}) \delta_{\text{diagonal}}$$

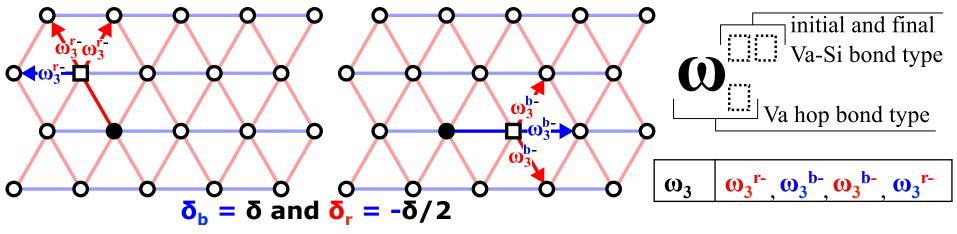
# Si-Va swing ( $\omega_1$ –type) under tetragonal strain



	Strain: +0.01			in: 0	Strain: -0.01	
(eV)	$\Delta E_1^{rr}$	1.18 ≈ 1.05+0.14			$\Delta E_1^{\rm rr}$	0.92 ≈ 1.05-0.14
	$\Delta E_1^{\rm rb}$	0.98 ≈ 1.05-0.07	$\Delta E_1$	1.05	$\Delta E_1^{\rm rb}$	1.11 ≈ 1.05+0.07
Barrier	$\Delta E_1^{\rm br}$	0.98 ≈ 1.05-0.07			$\Delta E_1^{\rm br}$	1.11 ≈ 1.05+0.07

Si-Va re-orientation can happen faster along particular directions  $\Delta E_1(\delta) \approx \Delta E_1(0) - (14 {\rm eV}) \delta_{\rm diagonal}$ 

Si-Va dissociation jump ( $\omega_3$  –type) under tetragonal strain

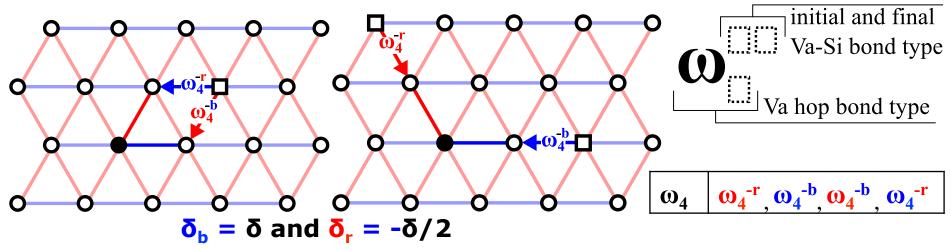


- Blue Jumps ( $\Delta E_3$ ) increase (decrease) for  $\delta > 0$  (<0)
- Red Jumps ( $\Delta E_3$ ) decrease (increase) for  $\delta > 0$  (<0)

	Strain: +0.01		Strain: 0		Strain: -0.01	
	$\Delta E_3^{b-}$	1.41 ≈ 1.27+0.14			$\Delta E_3^{b-}$	1.12 ≈ 1.27-0.14
(eV)	$\Delta E_3^{r-}$	1.40 ≈ 1.27+0.14	$\Delta E_3$	1.27	$\Delta E_3^{r-}$	1.11 ≈ 1.27-0.14
Barrier	$\Delta E_3^{r-}$	1.18 ≈ 1.27-0.07			$\Delta E_3^{r-}$	1.34 ≈ 1.27+0.07
Ba	$\Delta E_3^{b-}$	1.18 ≈ 1.27-0.07			$\Delta E_3^{b-}$	1.34 ≈ 1.27 - 0.07

 $\Delta E_3(\delta) \approx \Delta E_3(0) - (14 \text{eV}) \delta_{\text{diagonal}}$ 

Si-Va association jump ( $\omega_4$  –type) under tetragonal strain



- Blue Jumps ( $\Delta E_4$ ) increase (decrease) for  $\delta > 0$  (<0)
- Red Jumps ( $\Delta E_4$ ) decrease (increase) for  $\delta > 0$  (<0)

	Strain: +0.01		Strain: 0		Strain: -0.01	
	$\Delta E_4^{-b}$	1.29 ≈ 1.16+0.14			$\Delta E_4^{-b}$	1.02 ≈ 1.16-0.14
. (eV)	$\Delta E_4^{-r}$	1.29 ≈ 1.16+0.14	$\Delta E_4$	1.16	$\Delta E_4^{-r}$	1.00 ≈ 1.16-0.14
Barrier	$\Delta E_4^{-r}$	1.09 ≈ 1.16-0.07			$\Delta E_4^{-r}$	1.21 ≈ 1.16+0.07
Bč	$\Delta E_4^{-b}$	1.08 ≈ 1.16-0.07			$\Delta E_4^{-b}$	1.22 ≈ 1.16+0.07

 $\Delta E_4(\delta) \approx \Delta E_4(0) - (14 \text{eV}) \delta_{\text{diagonal}}$ 

#### Summary: All jump barriers under tetragonal strain 1.6 $\Delta E_1(\delta)$ $\Delta E_{2}(\delta)$ $\Delta E_{-}(\delta)$ 1.4 δ Barrier height, AE (eV) it line ΔE.(δ line AE.(8 fit line $\Delta E_{2}(\delta)$ fit line $\Delta E_{.}(\delta)$ .2 -2δ $d\Delta E \approx -14 \mathrm{eV}$ 0.8 $d\delta_L$ 0.6 -0.01 -0.005 0.005 0.01 0 Strain on Cage Diagonal, $\delta_r$ Blue jump Red jump

A constant  $\frac{d\Delta E}{d\delta_L}$  is found on all jump types  $\Delta E_j(\delta_L) \approx \Delta E_j(0) - 14 \text{eV} \delta_L$ Changes in the cage-diagonal explains the changes in the migration barriers

> The blue jumps:  $\Delta E_i(\delta) \approx \Delta E_i(0) + 14\text{eV} \delta$ The red jumps:  $\Delta E_i(\delta) \approx \Delta E_i(0) - 7\text{eV} \delta$

Symmetry enforces -2:1 ratio for derivative

### Kinetic Coupling: Self-Consistent Mean-Field Model

• Microscopic Master equation  

$$\begin{aligned} & \frac{d\hat{P}(\mathbf{n},t)}{dt} = \sum_{\tilde{\mathbf{n}}} \hat{W}(\tilde{\mathbf{n}} \rightarrow \mathbf{n}) \hat{P}(\tilde{\mathbf{n}},t) - \sum_{\mathbf{n}} \hat{W}(\mathbf{n} \rightarrow \tilde{\mathbf{n}}) \hat{P}(\mathbf{n},t) \\ & \text{at equilibrium} \qquad \hat{P}_0(\mathbf{n}) = \exp[\beta(\Omega_0 + \sum_{\alpha} \mu_{\alpha} \sum_i n_i^{\alpha} - \hat{H})] \\ & \text{with} \qquad \hat{H} = \frac{1}{2!} \sum_{\alpha,\beta,i\neq j} V_{ij}^{\alpha\beta} n_i^{\alpha} n_j^{\beta} + \frac{1}{3!} \sum_{\alpha,\beta,\gamma,i\neq j\neq k} V_{ijk}^{\alpha\beta\gamma} n_i^{\alpha} n_j^{\beta} n_k^{\gamma} + \dots \end{aligned}$$

 Under imposed chemical potential gradient: introduce effective interactions so as to satisfy steady state

$$\hat{P}(\mathbf{n},t) = \hat{P}_0(\mathbf{n})\hat{P}_1(\mathbf{n},t); \quad \hat{h}(t) = \frac{1}{2!}\sum_{\alpha,\beta,i\neq j} \upsilon_{ij}^{\alpha\beta}(t)n_i^{\alpha}n_j^{\beta} + \frac{1}{3!}\sum_{\alpha,\beta,\gamma,i\neq j\neq k} \upsilon_{ijk}^{\alpha\beta\gamma}(t)n_i^{\alpha}n_j^{\beta}n_k^{\gamma} + \cdots$$

$$\frac{d\left\langle n_{i}^{\alpha}\right\rangle}{dt} = -\sum_{s\neq i} J_{i\rightarrow s}^{\alpha} \text{ and } \frac{d\left\langle n_{i}^{\alpha}n_{j}^{\beta}\right\rangle}{dt} = 0$$

→ Linear system relating effective interactions and gradient of  $\mu$ 's

# Kinetic Coupling: Self-Consistent Mean-Field Model (2)

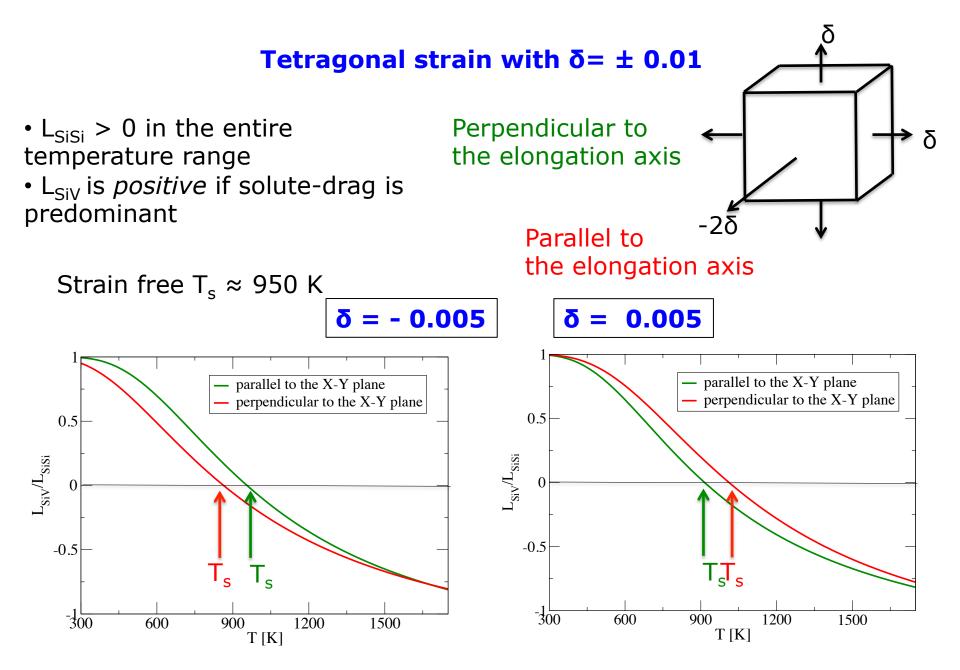
• The effective interactions contain the kinetic coupling terms

$$J_{i \to j}^{\alpha} = -L_{ij}^{(0)\alpha} \left( \delta \mu_{j}^{\alpha} - \delta \mu_{i}^{\alpha} \right) + \sum_{\sigma,s} L_{ijs}^{(1)\alpha\sigma} \left( \upsilon_{js}^{\alpha\sigma} - \upsilon_{is}^{\alpha\sigma} \right) + \dots$$
  
becomes 
$$J_{i \to j}^{\alpha} = -\sum_{\beta,s,s'} L_{ij,ss'}^{\alpha\beta} \left( \mu_{s'}^{\beta} - \mu_{s}^{\beta} \right) \qquad \Rightarrow \text{ full Onsager Matrix}$$

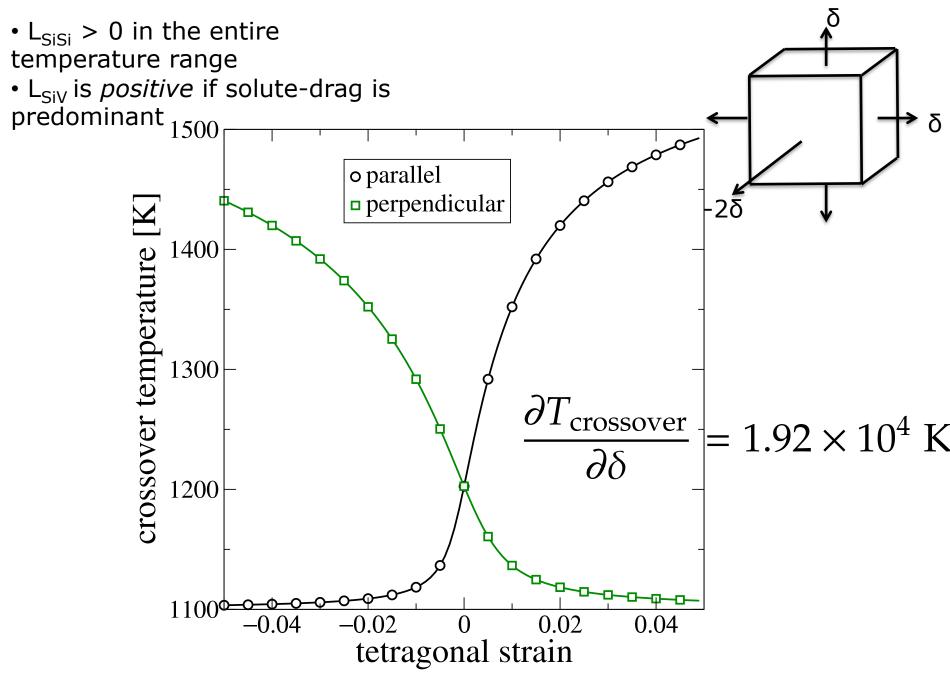
- Approach can be extended to arbitrary crystallographic structures
- Requires knowledge of atomic jump frequencies
- ➔ Allows for including stress effects on kinetics:

e.g., creep, transport near dislocations

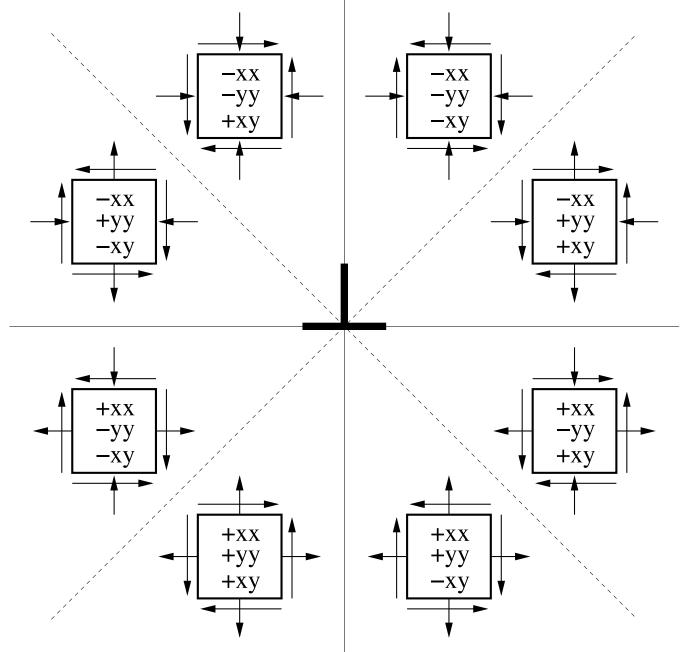
#### Anisotropy in solute drag due to tetragonal strain



## Anisotropy in solute drag due to tetragonal strain



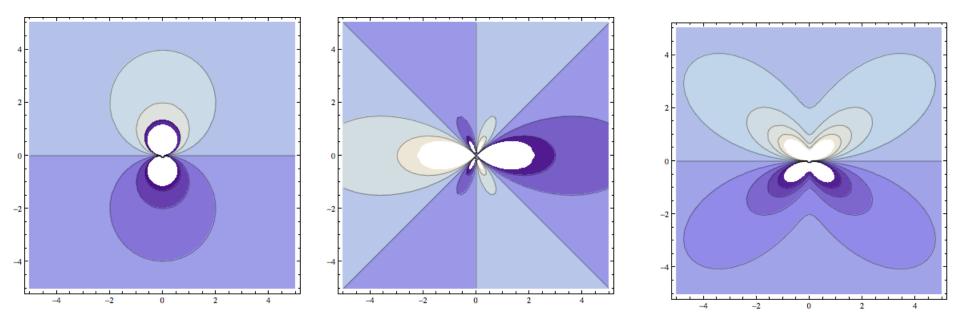
#### Dislocation strain field



### **Dislocation strain field**

 $\varepsilon_{\text{volumetric}} = -\frac{b}{4\pi r} \sin \theta$  $\gamma_{\text{shear}} = \frac{b}{4\pi r} \frac{3}{2} \cos \theta \cos 2\theta$ 

$$\varepsilon_{\rm bb} = -\frac{b}{4\pi r} \left( 2\sin\theta + \frac{3}{2}\sin\theta\cos2\theta \right)$$

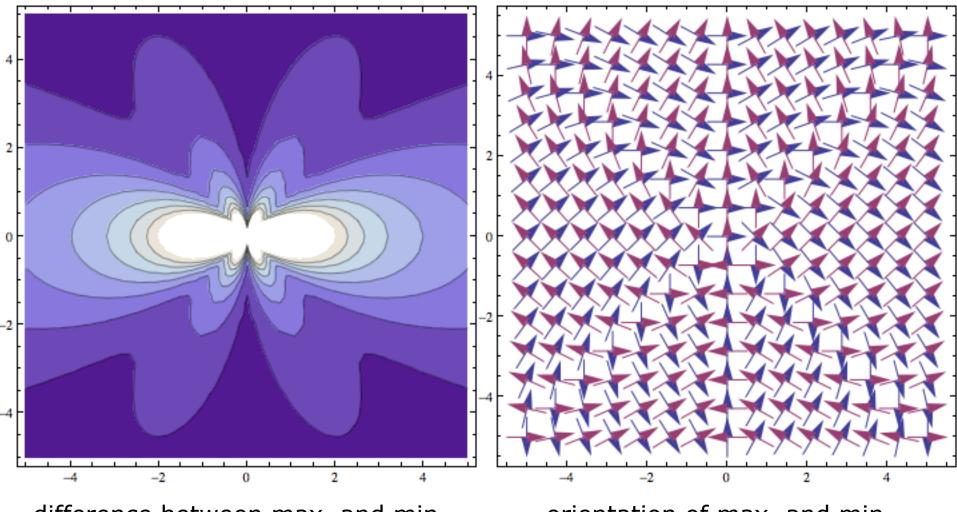


Anisotropy in L<sub>SiV</sub> due to dislocation strain field  

$$\varepsilon_{\text{volumetric}} = -\frac{b}{4\pi r} \sin \theta$$
  
 $\gamma_{\text{shear}} = \frac{b}{4\pi r} \frac{3}{2} \cos \theta \cos 2\theta$   
 $\varepsilon_{\text{bb}} = -\frac{b}{4\pi r} \left(2\sin \theta + \frac{3}{2}\sin \theta \cos 2\theta\right)$   
 $\left(L_0 + \frac{1}{3}L'_v \varepsilon_{\text{volumetric}} + \frac{1}{6}L'_{\text{tet}} \varepsilon_{\text{bb}} - \frac{2}{3}L'_{\text{tet}} \gamma_{\text{shear}} - \frac{2}{3}L'_v \varepsilon_{\text{volumetric}}\right)$ 

L0: unstrained L  $L'_v$ : volumetric strain derivative  $L'_{tet}$ : tetragonal strain derivative

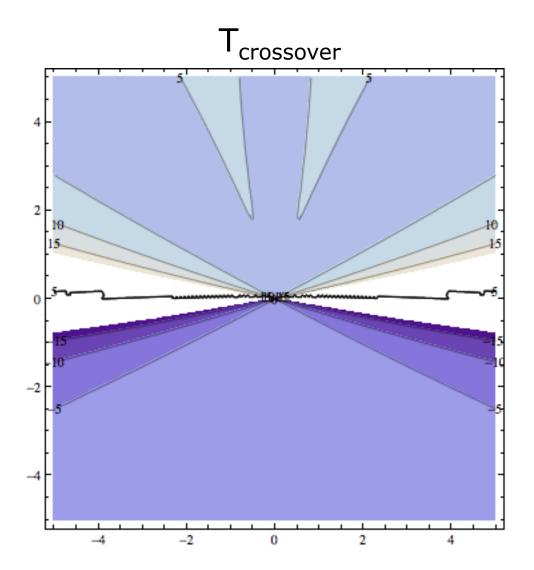
# Anisotropy in $L_{\mbox{\scriptsize SiV}}$ due to dislocation strain field



difference between max. and min. eigenvalue of Lij

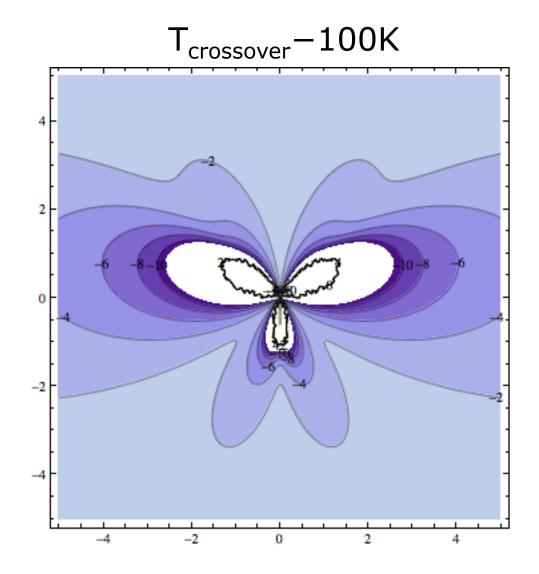
orientation of max. and min. eigenvectors of Lij

Anisotropy in  $L_{SiV}$  relative to average  $L_{SiV}$  at crossover



unstrained L nearly 0: ratio nearly distance independent

# Anisotropy in $L_{SiV}$ relative to average $L_{SiV}$ below crossover



extremely large anisotropies near core unusual contours should affect solute distribution Anisotropy in  $L_{SiV}$  relative to average  $L_{SiV}$  above crossover  $T_{crossover}$ +100K

> extremely large anisotropies near core unusual contours should affect solute distribution

0

2

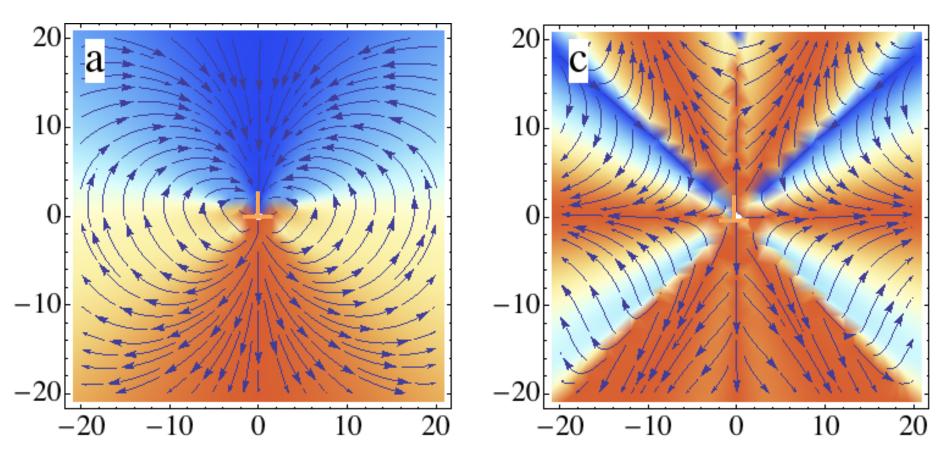
4

-2

# Initial flow streams at T<sub>crossover</sub>

#### vacancy

silicon

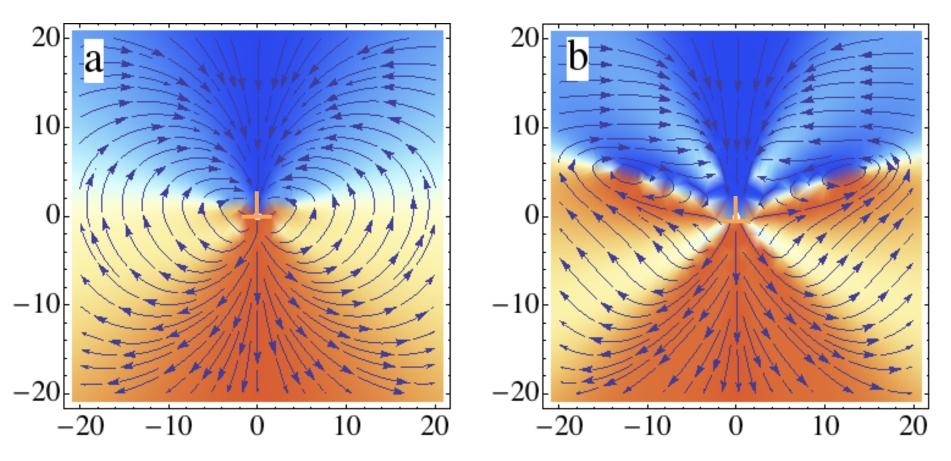


strong directionality from primary anisotropy at crossover

# Initial flow streams at $T_{crossover}$ – 50K

#### vacancy

silicon

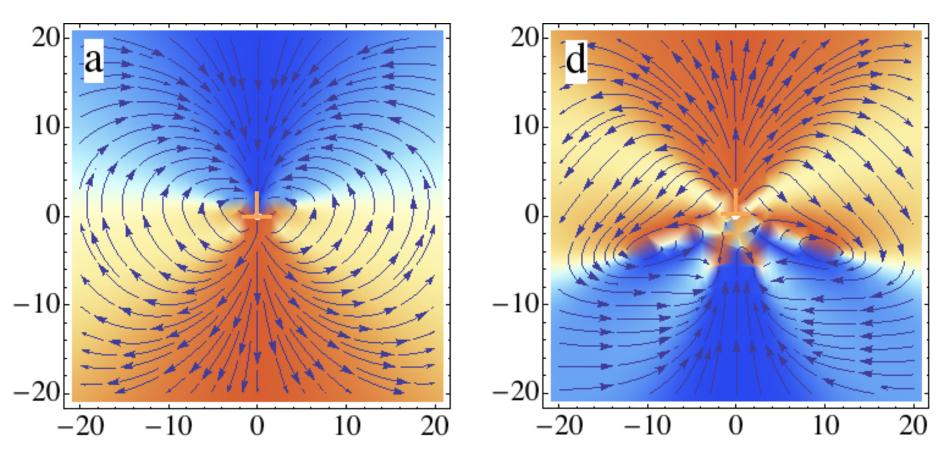


solute drag into core in anisotropic pattern

# Initial flow streams at $T_{crossover}$ +50K

#### vacancy

silicon



depletion of solute from dislocation core above crossover (solute exchange)

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Materials Science and Engineering, Univ. Illinois, Urbana-Champaign CEA Saclay, Service de Recherches de Métallurgie Physique, France

Goal: Predict solute and defect evolution near a dislocation

Transport of point defects near dislocations (sinks)

# Under irradiation: continuous transport of defect fluxes to sinks

- Coupling of defects and solutes fluxes?
- Segregation, precipitation, creep?

#### Stresses of dislocation and applied

- Inhomogeneous driving forces
- Inhomogeneous anisotropic mobilities

System: substitutional Si in Ni

#### Approach:

- Ab initio calculation of migration barriers
- Self-consistent mean-field method



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